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PATENT NUMBER and  
ISSUE DATE

U.S. UTILITY Patent Application

APPL. NO.	10/34745	FILING DATE	01/14/2002	CLASS	156(42)	SUBCLASS		GAU	4733	EXAMINER	
**APPLICANTS: Sharan Sujit; Sandhu Gurtej; Smith Paul; Chang Mei;											
**CONTINUING DATA VERIFIED: THIS APPLICATION IS A DIV OF 09/026,042 02/19/1998											
** FOR THIS APPLICATION IS VERIFIED:											
PG-PUB	<input type="checkbox"/> DO NOT PUBLISH		RESCIND								
Foreign priority claimed			<input type="checkbox"/> yes <input type="checkbox"/> no		ATTORNEY DOCKET NO						
35 USC 119 conditions met			<input type="checkbox"/> yes <input type="checkbox"/> no		MI22-1902						
Verified and Acknowledged Examiners's initials											
TITLE : RF powered plasma enhanced chemical vapor deposition reactor and methods of effecting plasma enhanced chemical vapor deposition											
U.S. DEPT. OF COMM./PAT. & TM-PTO-16L (Rev. 12-94)											

NOTICE OF ALLOWANCE MAILED		Assistant Examiner	CLAIMS ALLOWED	
			Total Claims	Print Claim for O.G
ISSUE FEE		Primary Examiner	DRAWING	
Amount Due	Date Paid		Sheets Drwg.	Figs. Drwg.
TERMINAL DISCLAIMER		PREPARED FOR ISSUE		Applicant Examiner
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